

INFORMATION DISCLOSURE CITATION

Atty. Docket No. 08409.0047	Serial No. 10/733,230
Applicant Tuung Luoh et al.	
Filing Date December 12, 2003	Group: 1765

U.S. PATENT DOCUMENTS

Examiner Initials	Document Number	Issue Date	Name	Class	Sub Class	Filing Date If Appropriate
DL	5,914,896	June 22, 1999	Lee et al.	365	185.19	
DL	6,381,670	April 30, 2002	Lee et al.	711	103	

FOREIGN PATENT DOCUMENTS

Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

DL	Seiichi Mori et al., "Polyoxide Thinning Limitation and Superior ONO Interpoly Dielectric for Nonvolatile Memory Devices", IEEE TRANSACTIONS ON ELECTRON DEVICES, Vol. 38, No. 2, February 1991, pp. 270-277
DL	Seiichi Mori et al., "ONO Inter-Poly Dielectric Scaling for Nonvolatile Memory Applications", IEEE TRANSACTIONS ON ELECTRON DEVICES, Vol. 38, No. 2, February 1991, pp. 386-391

Examiner <i>[Signature]</i>	Date Considered 2/14/05
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*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.